

Amendments to the Specification:

Please amend paragraph [0029] as follows:

[0029] Referring again to Figure 21, one or more elements of the reduction lens system 140 can be coupled to a lens actuator 141 to move axially relative to the reticle 130 and the substrate support 150 under the control of the controller 170. Moving elements of the reduction lens system 140 can provide another degree of freedom for positioning the focal plane of the radiation beam 128 relative to the layer 161 on the microlithographic substrate 160. Accordingly, the reduction lens system 140 can move in combination with or in lieu of moving the microlithographic substrate 160 to vary the axial position of the focal plane relative to the layer 161.

Please amend paragraph [0032] as follows:

[0032] Figure 4 is a partially schematic illustration of a portion of an apparatus 410 that includes a substrate support 450 carrying the microlithographic substrate 160. The apparatus 400 further includes a reticle 430 oriented at a non-normal (i.e., oblique) tilt angle 433 relative to a radiation beam ~~480~~428 traveling along a radiation path 480 in a first direction 481. The radiation passes through the reticle 430 and through a reducing lens 440 to impinge on the microlithographic substrate 160 in second direction 482.